

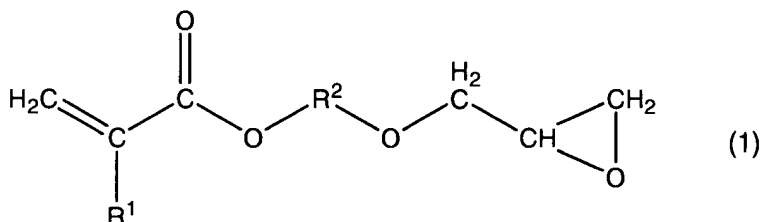
A) Amendments to the claims:

1. (currently amended) A photosensitive resin composition ~~characterized by~~ comprising

a poly((meth)acrylic acid)-based water-soluble photo-sensitive resin (A)

having an acid value of 150 mgKOH/g or more on a solid basis;

the resin (A) being formed of a ((meth)acrylic acid)-based polymer in which a compound represented by formula (1):



(wherein R¹ represents H or Me; and R² represents a ~~linear~~ linear or branched C2-C10 alkylene group) has been added to portions of the carboxylic groups,

a photopolymerization initiator (B); and

water (C).

2. (original) A photosensitive resin composition according to claim 1, wherein the carboxyl groups of the ((meth)acrylic acid)-based polymer to which the compound represented by formula (1) has not been added are at least partially neutralized with an alkali.

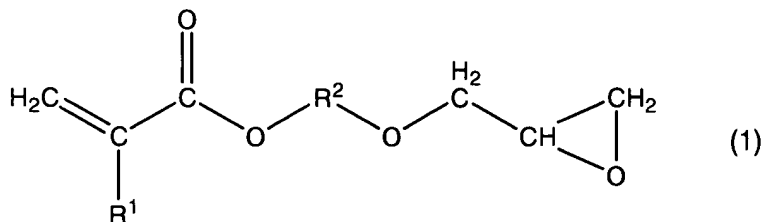
3. (currently amended) A method for forming a hydrogel characterized by comprising subjecting a photosensitive resin composition as recited in claim 1 ~~or 2~~ to photopolymerization.

4. (currently amended) A hydrogel ~~characterized by being~~ produced by causing a photosensitive resin composition to photopolymerize, the photosensitive resin composition comprising

a poly((meth)acrylic acid)-based water-soluble photo-sensitive resin (A)

having an acid value of at least about 170 mgKOH/g on a solid basis;

the resin (A) being formed of a ((meth)acrylic acid)-based polymer in which a compound represented by formula (1):



(wherein R¹ represents H or Me; and R² represents a ~~linear~~ linear or branched C2-C10 alkylene group) has been added to portions of the carboxylic groups,
a photopolymerization initiator (B); and
water (C).

5. (currently amended) A hydrogel according to claim 4, wherein the carboxyl groups of the ((meth)acrylic acid)-based polymer to which the compound represented by formula (1) has not been added are at least partially ~~or entirely~~ neutralized with an alkali.